110 Depositing a silicide layer on a source and drain area. 120 Implanting a dopant in the source and drain area. 130-Performing a diffusion process on the source and drain area.

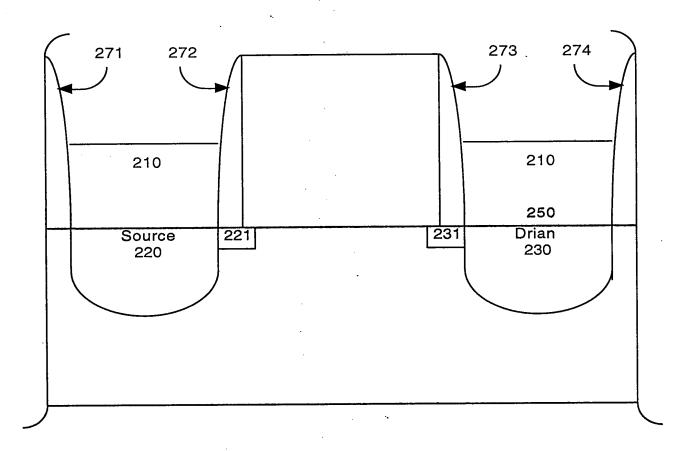


FIG 2A

